



Cornell University
Laboratory for Elementary-Particle Physics



Detailed Characterization of Vacuum Chamber Surface Properties

Using Measurements of the Time Dependence of Electron Cloud Development

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Cornell Laboratory for Accelerator-Based Sciences and Education

CESRTA Advisory Committee

11 September 2012



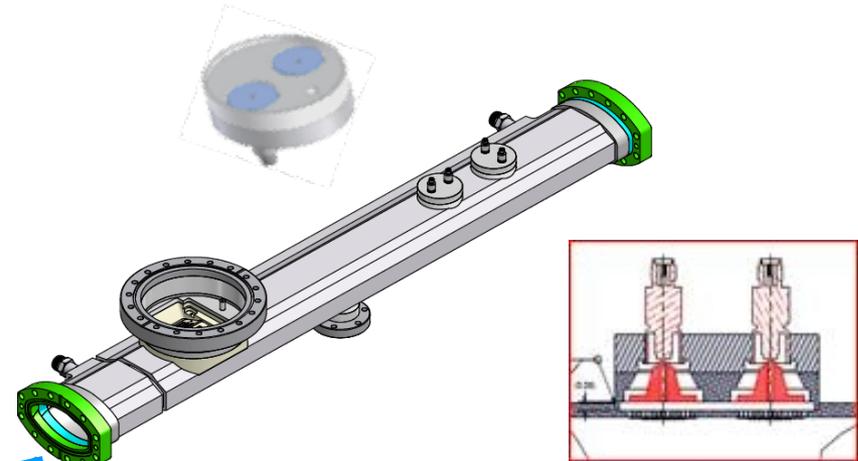
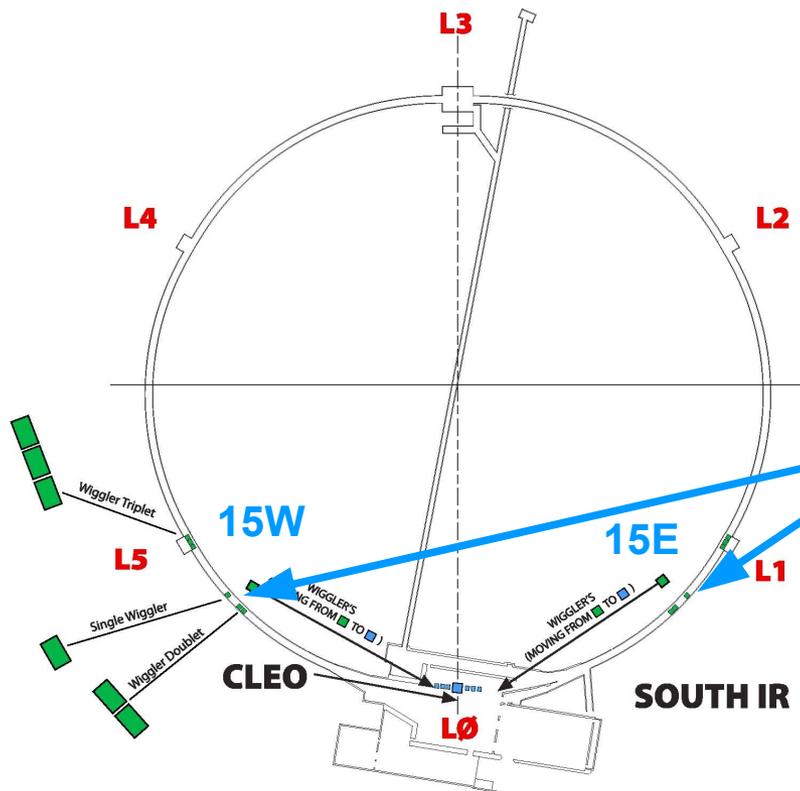


L3 Electron cloud experimental region

PEP-II EC Hardware: Chicane, SEY station
Four time-resolved RFA's
Drift and quadrupole diagnostic chambers

New electron cloud experimental regions in arcs (after 6 wigglers moved to L0 straight)

Locations for collaborator experimental vacuum chambers equipped with shielded pickup detectors



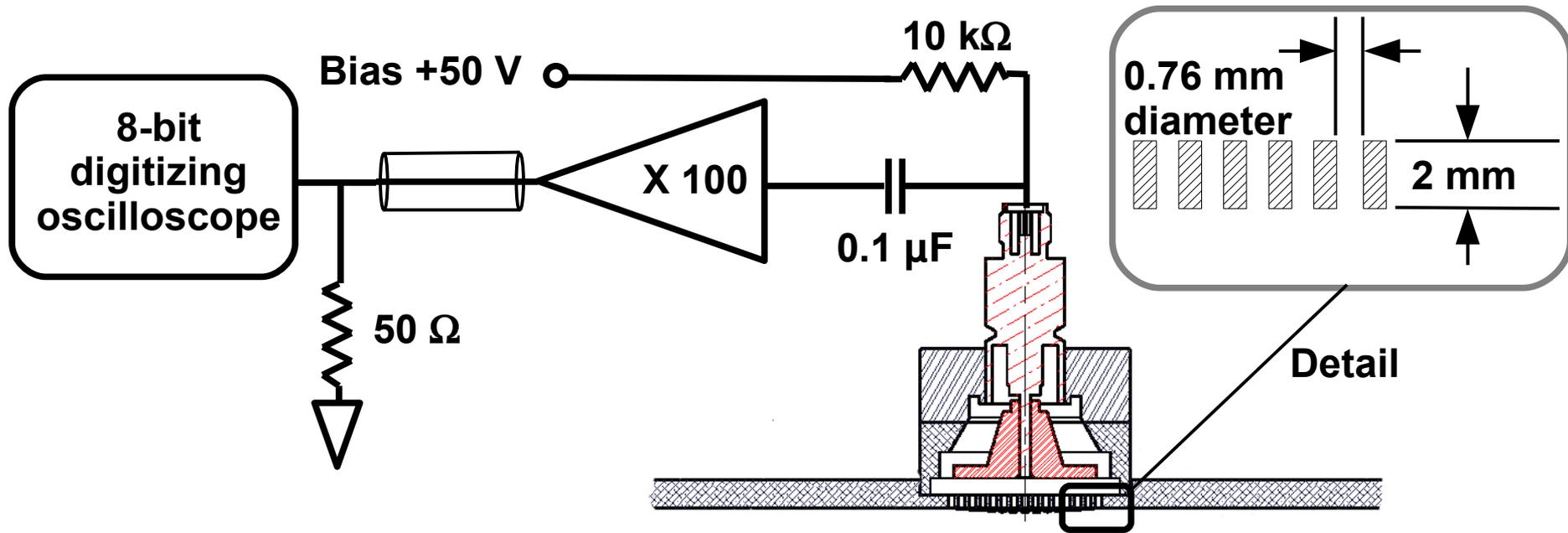
Custom vacuum chambers with shielded pickup detectors

Uncoated aluminum, and TiN, amorphous carbon, diamond-like carbon coatings

30 RFA's in drift regions, dipoles, quadrupoles, and wigglers



Shielded Pickup Design and Readout



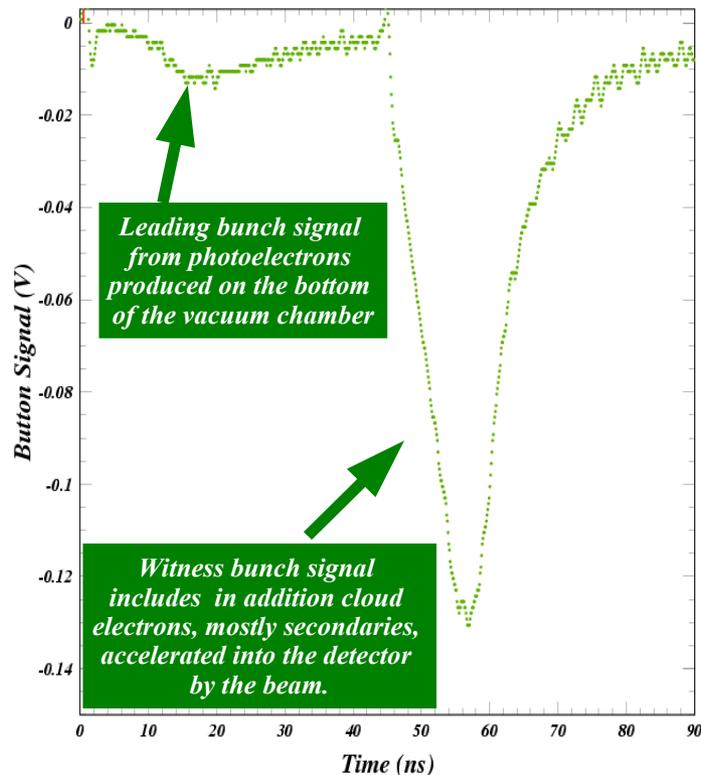
The pickup electrodes are shielded by the vacuum chamber hole pattern against the beam-induced signal.

The +50 V bias ensures that secondaries produced on the electrode do not escape.

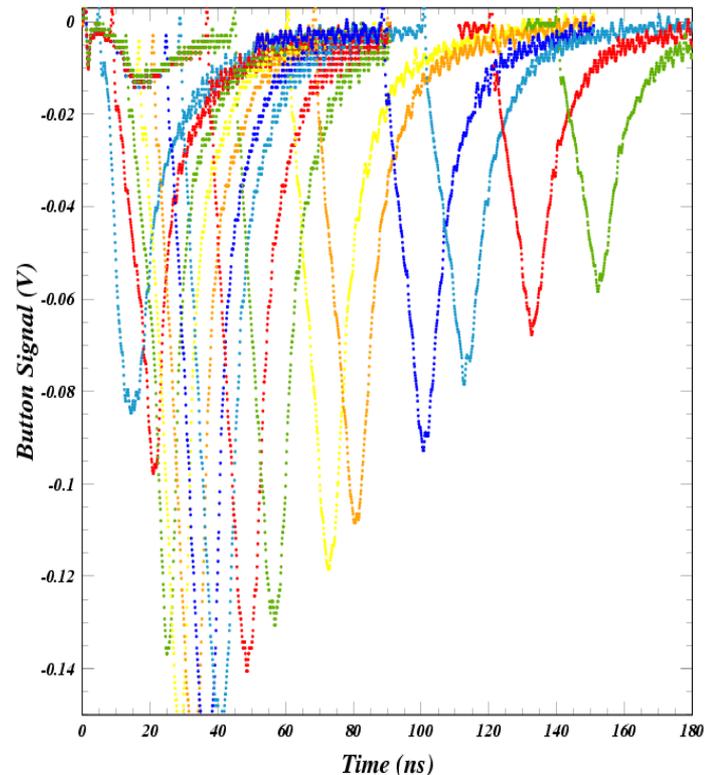
The digitized signal is an average over 8k triggers in time intervals of 0.1 ns.



*Shielded pickup scope trace
for two bunches 44 ns apart*



*Superposition of 15 such traces
illustrating the sensitivity to cloud lifetime*



The single bunch signal arises from photoelectrons produced on the bottom of the vacuum chamber. Its shape is closely related to the photoelectron kinetic energy distribution and the beam kick. The witness bunch signal includes the single-bunch signal as well as the that produced by cloud particles accelerated into the shielded pickup by the kick from the witness bunch. The witness signal is therefore sensitive to SEY.



* Originated at CERN in the late 1990's

* Widespread application for PS, SPS, LHC, KEK, RHIC, ILC ...

* Under active development at Cornell since 2008

* Successful modeling of CESR-TA tune shift measurements

* Interactive shielded pickup model implemented in 2010

* Full POSINST SEY functions added as option 2010-2012

* Flexible photoelectron energy distributions added 2011

* Synrad3D photon absorption distribution added 2011

I. Generation of photoelectrons

A) Production energy, angle

B) Azimuthal distribution (v.c. reflectivity)

II. Time-sliced cloud dynamics

A) Cloud space charge force

B) Beam kick

C) Magnetic fields

III. Secondary yield model

A) True secondaries (yields > 1!)

B) Rediffused secondaries (high energy)

C) Elastic reflection (dominates at low energy)

IV. Shielded pickup model

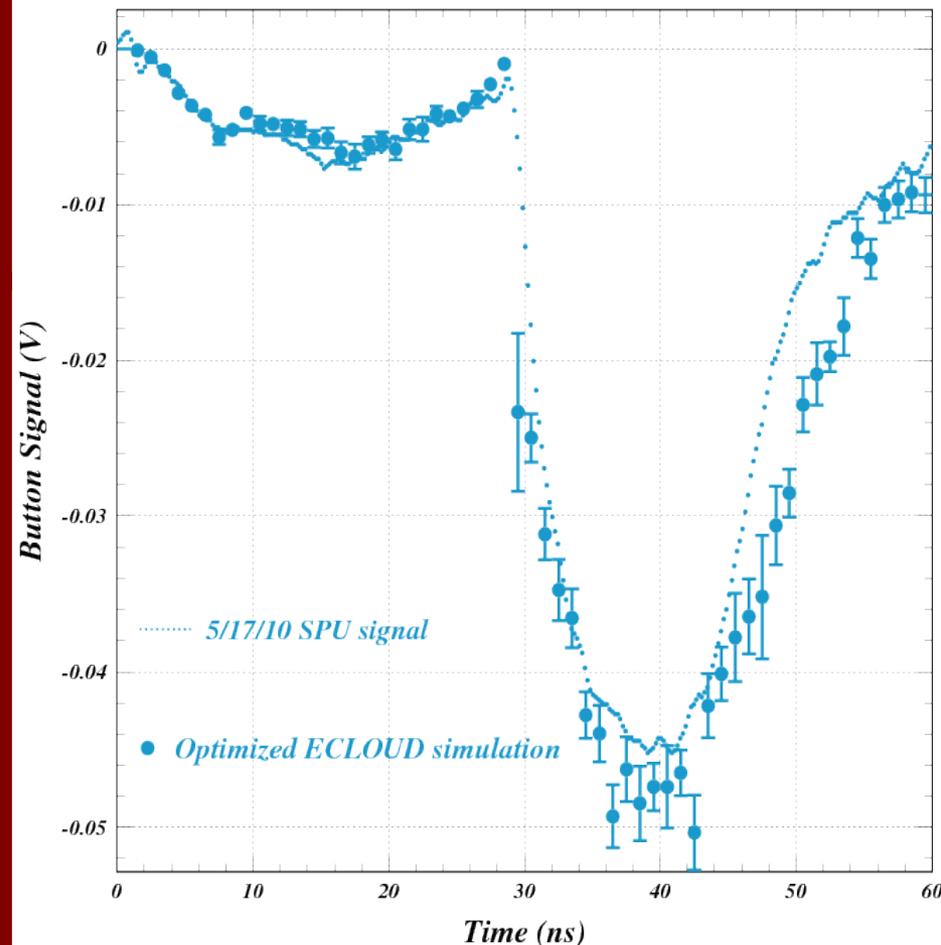
A) Acceptance vs incident angle, energy

B) Signal charge removed from cloud

C) Non-signal charge creates secondaries

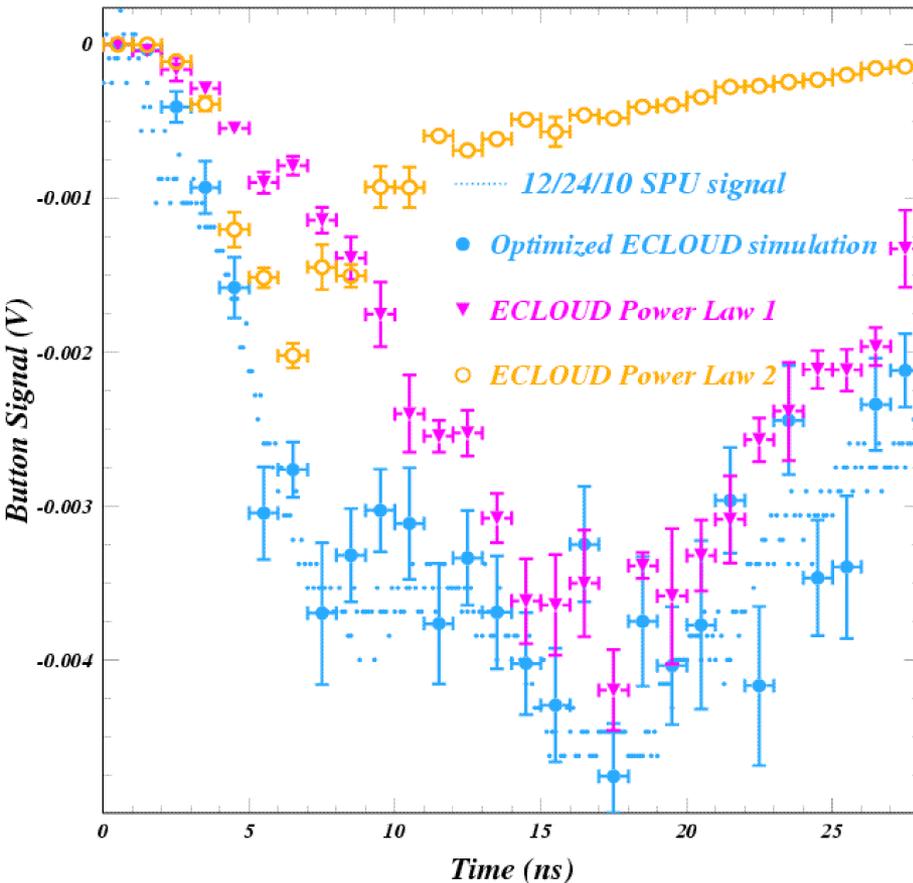
Modeled Signal

Counting signal macroparticles in each time slice
gives the statistical uncertainty shown





The shape of the signal from the leading bunch is determined by the photoelectron production energy distribution.



Two Power-Law Contributions

$$F(E) = E^{P_1} / (1 + E/E_0)^{P_2}$$

$$E_0 = E_{peak} (P_2 - P_1) / P_1$$

This level of modeling accuracy was achieved with the photoelectron energy distribution shown below, using a sum of two power law distributions.

$$E_{peak} = 80 \text{ eV} \quad P_1 = 4 \quad P_2 = 8.4$$

The high-energy component (22%) has a peak energy of 80 eV and an asymptotic power of 4.4. Its contribution to the signal is shown as yellow circles in the lower left plot.

$$E_{peak} = 4 \text{ eV} \quad P_1 = 4 \quad P_2 = 6$$

The low-energy component (78%) has a peak energy of 4 eV and an asymptotic power of 2. Its contribution to the signal is shown as pink triangles.

Electron Cloud Buildup Models and Plans at CESRTA
JAC et al, LCWS11
Recent Developments in Modeling Time-resolved Shielded-pickup Measurements of Electron Cloud Buildup at CESRTA
JAC et al, IPAC11



$$f(E_{sec}) \sim E_{sec} \exp(-E_{sec}/E_{SEY})$$

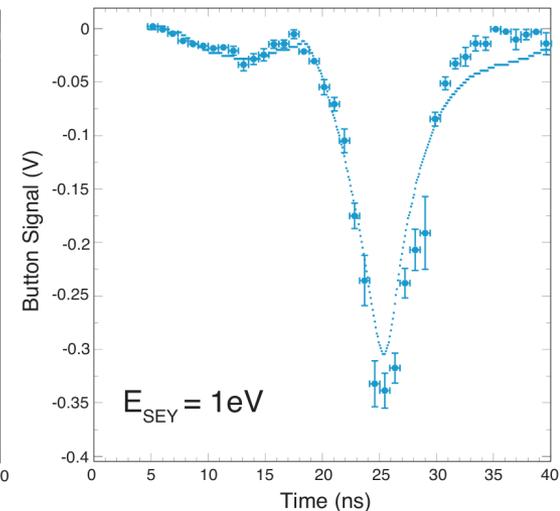
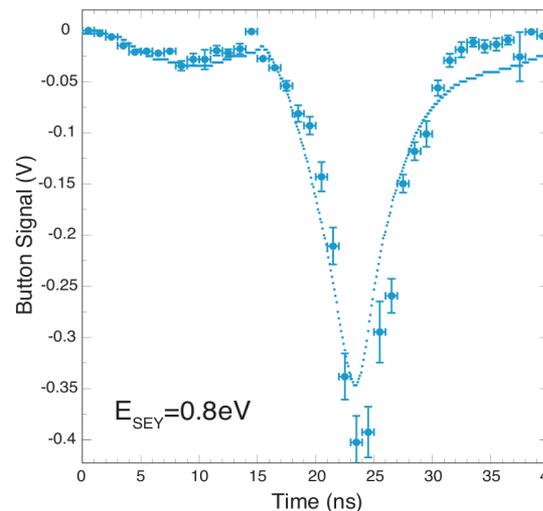
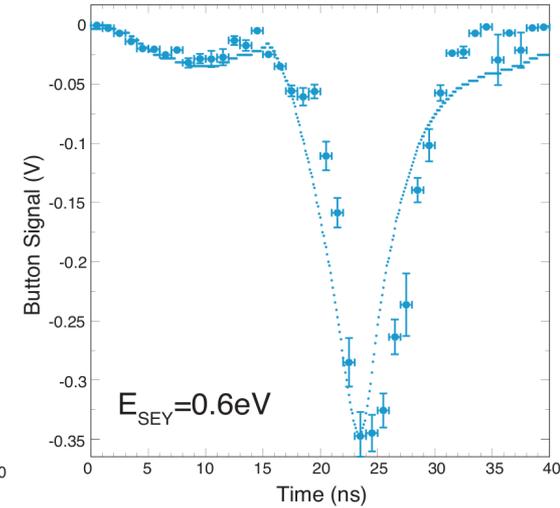
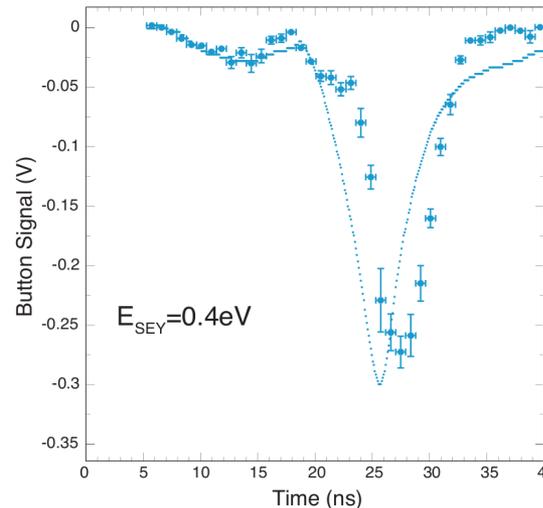
The time development of the cloud is directly dependent on secondary kinetic energies and therefore on the relative probabilities of the three secondary production processes:

- 1) True secondaries dominate at high incident energy and are produced at low energy*
- 2) Rediffused secondaries are produced at energies ranging up to the incident energy*
- 3) Elastic scattering dominates at low incident energy*

The CESRTA Test Accelerator Electron Cloud Research Program
Phase 1 Report
M.A.Palmer et al, August, 2012

Recent Developments in Modeling Time-resolved Shielded-pickup
Measurements of Electron Cloud Buildup at CESRTA
JAC et al, IPAC11

Electron Cloud Buildup Models and Plans at CESRTA
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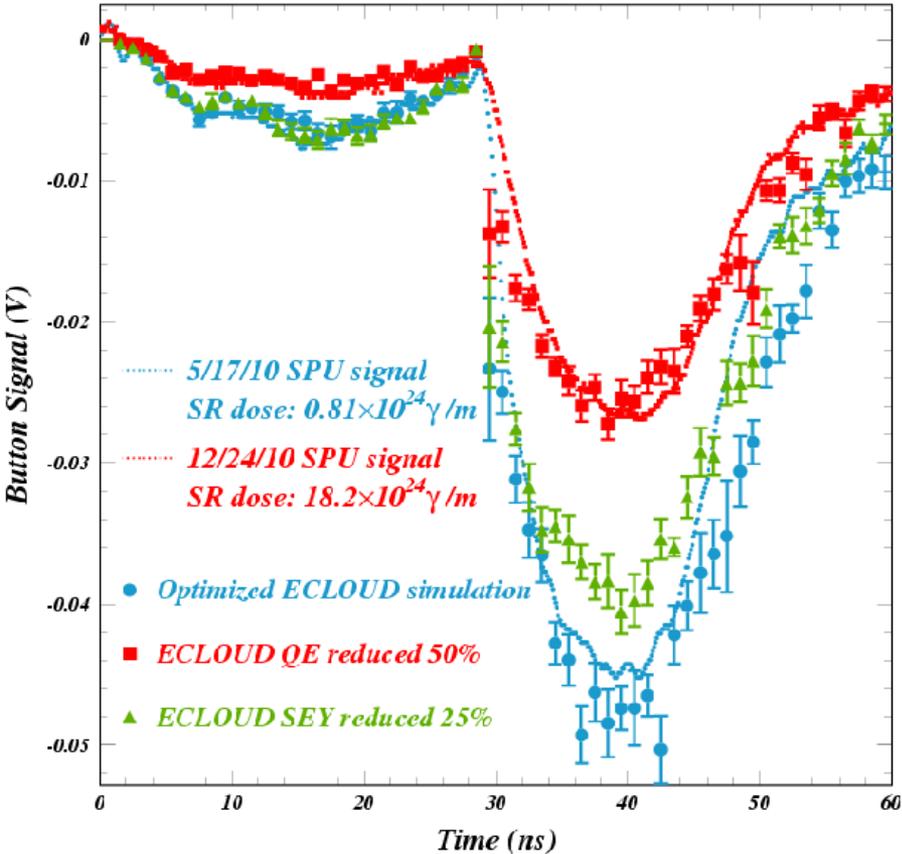


The pulse shape for the 14-ns witness bunch signal sets a lower bound on the model parameter E_{SEY} .

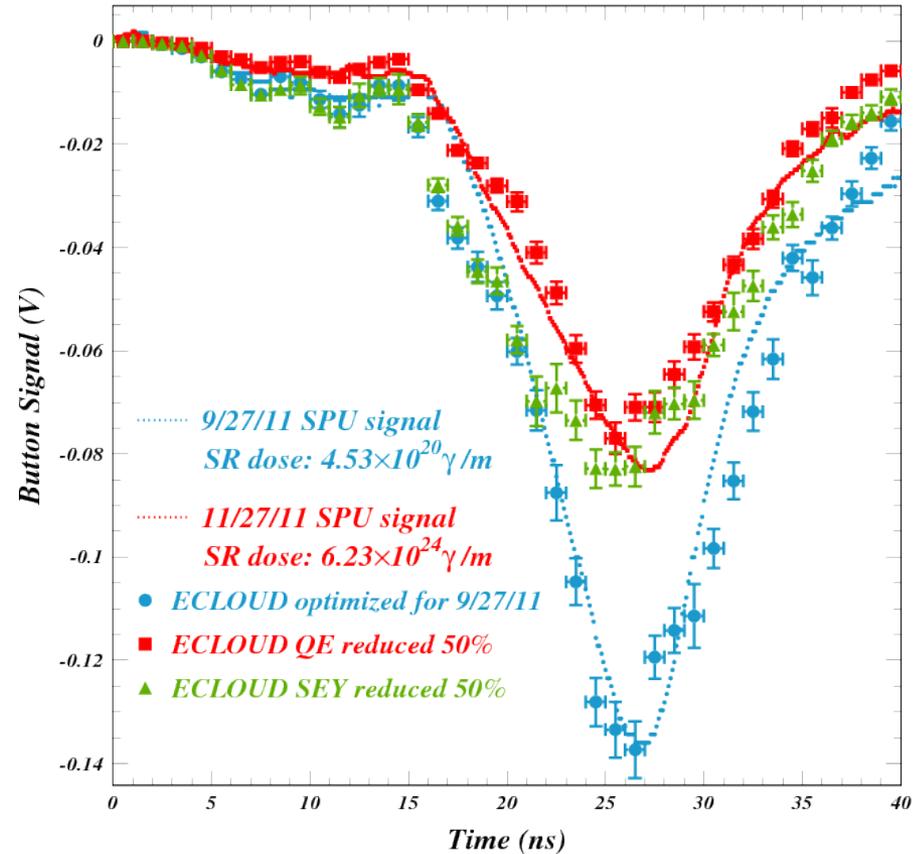


Beam conditioning effects on an amorphous carbon coating

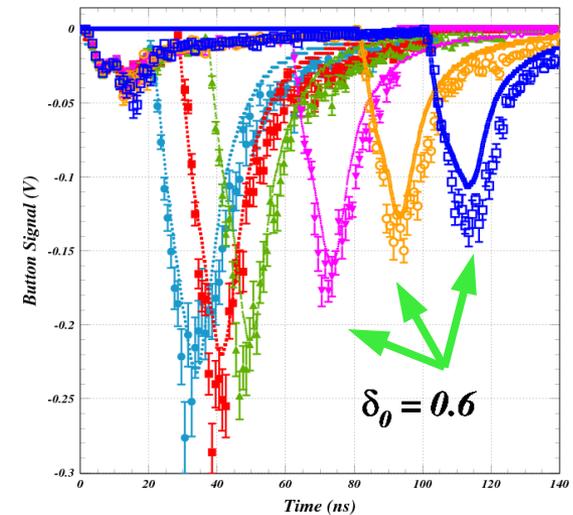
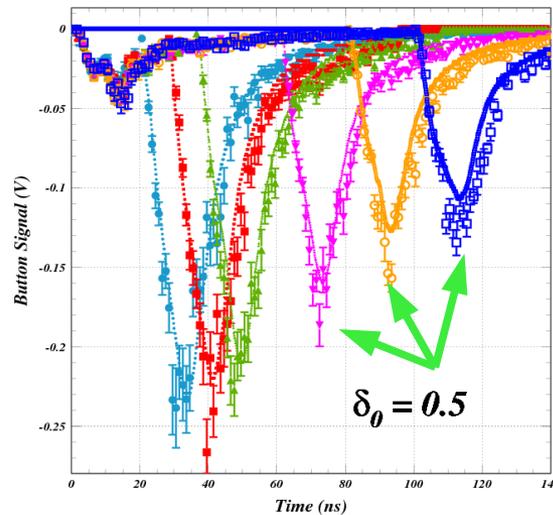
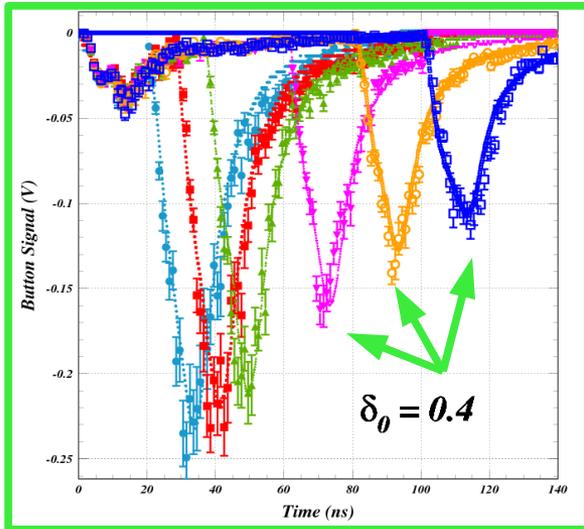
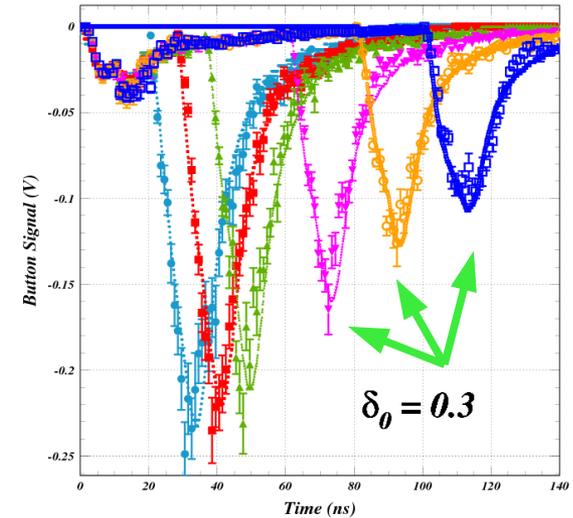
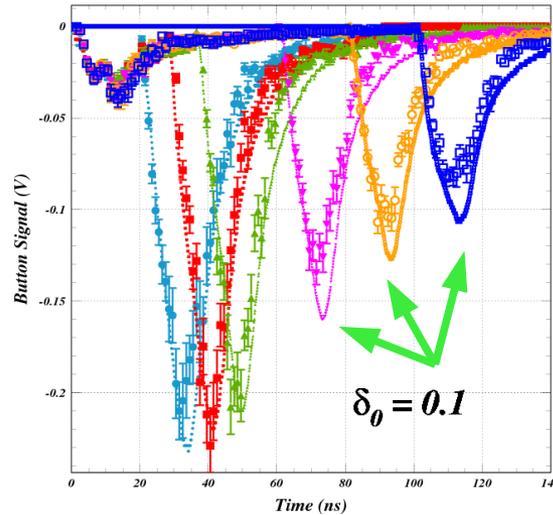
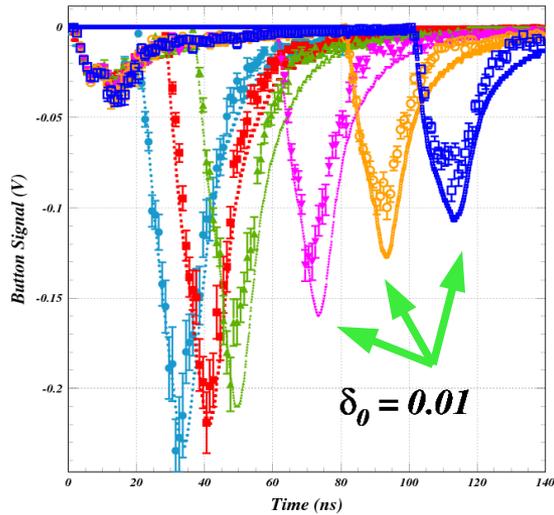
Recent Developments in Modeling Time-resolved Shielded-pickup Measurements of Electron Cloud Buildup at CESRTA
JAC et al, IPAC11



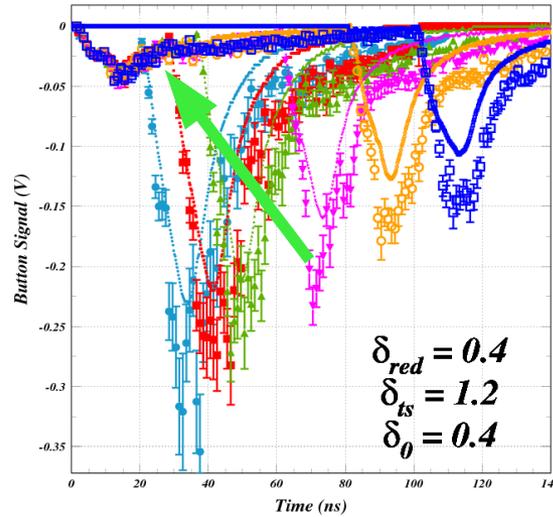
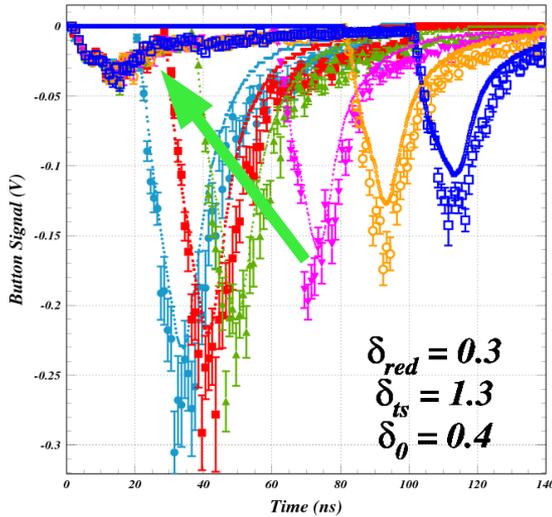
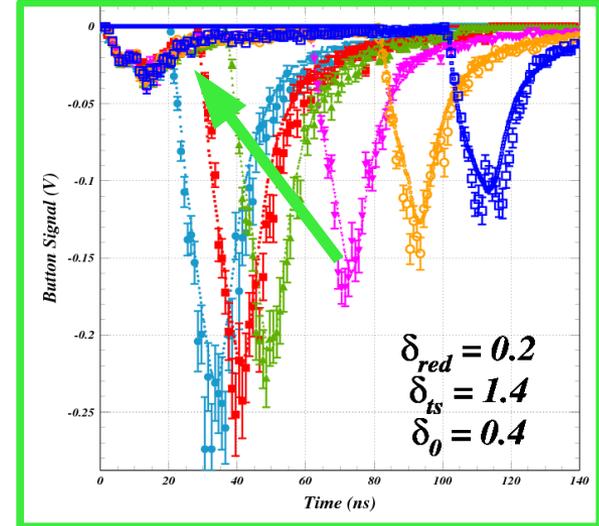
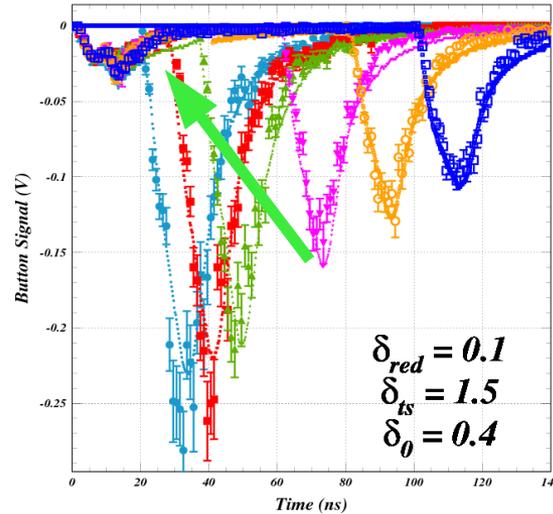
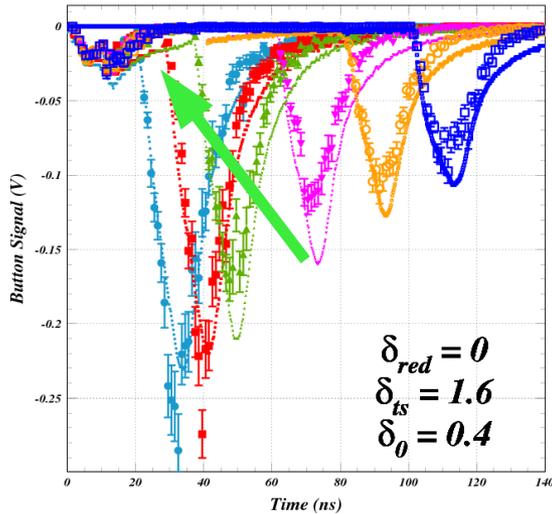
Time-resolved Shielded-pickup Measurements and Modeling of Beam Conditioning Effects on Electron Cloud Buildup at CESRTA
JAC et al, IPAC12



The beam conditioning effect for an amorphous carbon coating is primarily in quantum efficiency in both the early and late conditioning processes.



The later witness bunches provide sensitivity to the value for elastic yield.



The rediffused secondary yield process determines the trailing edge of the signal from a single bunch.

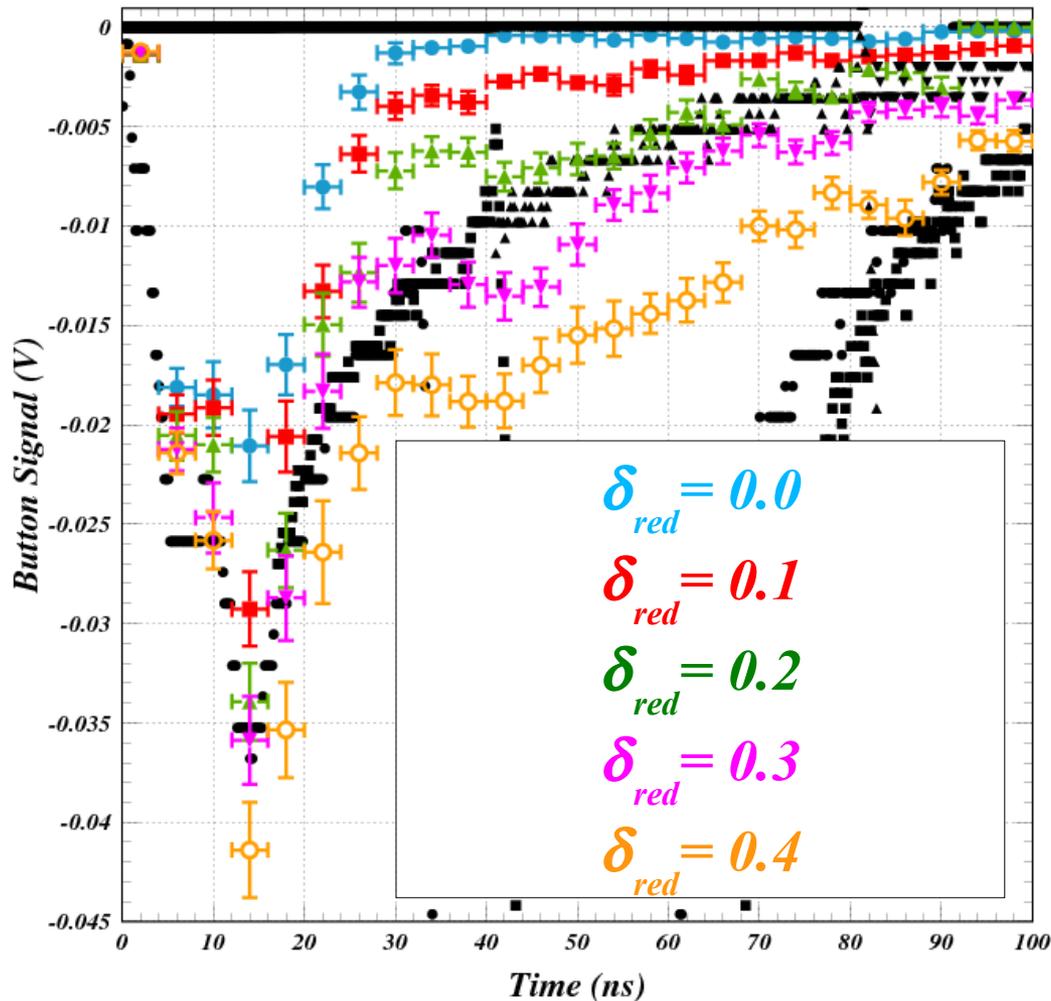
This trailing edge is insensitive to δ_0 , as seen on slide 9.

The late witness bunch signal used to determine δ_0 is also sensitive to the rediffused yield process.

The witness bunch method provides discriminating power between the true and rediffused processes.



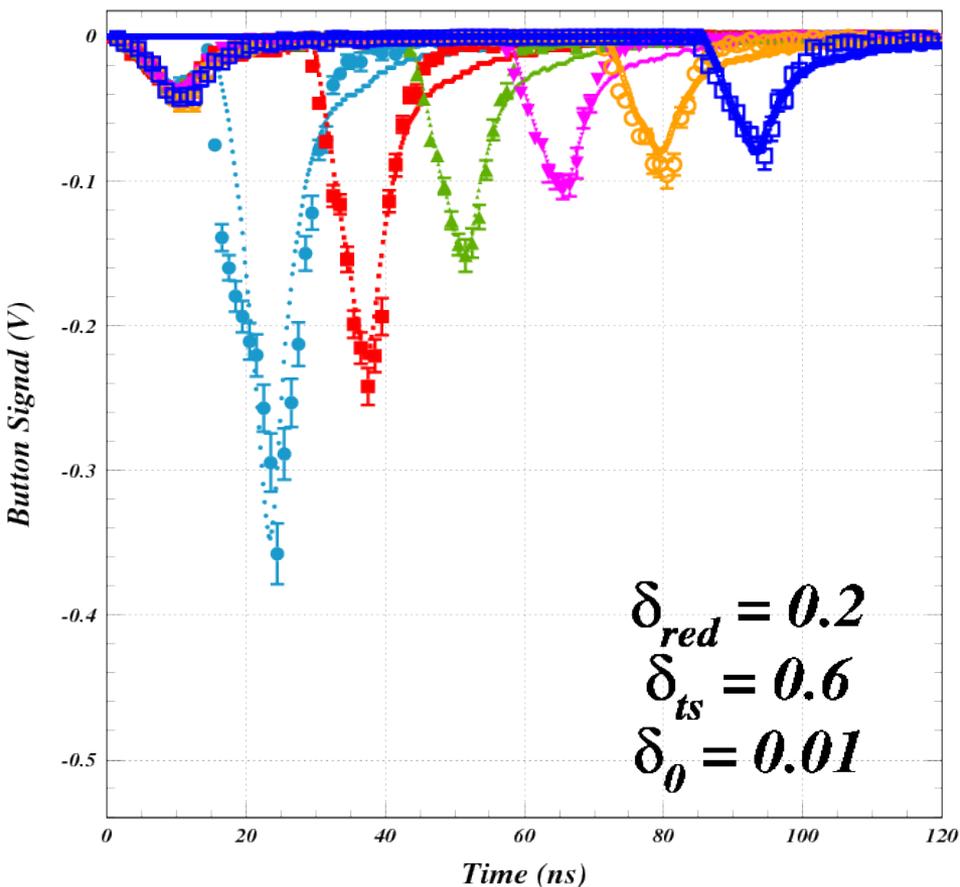
Sensitivity to the yield value for the rediffused component of secondary emission



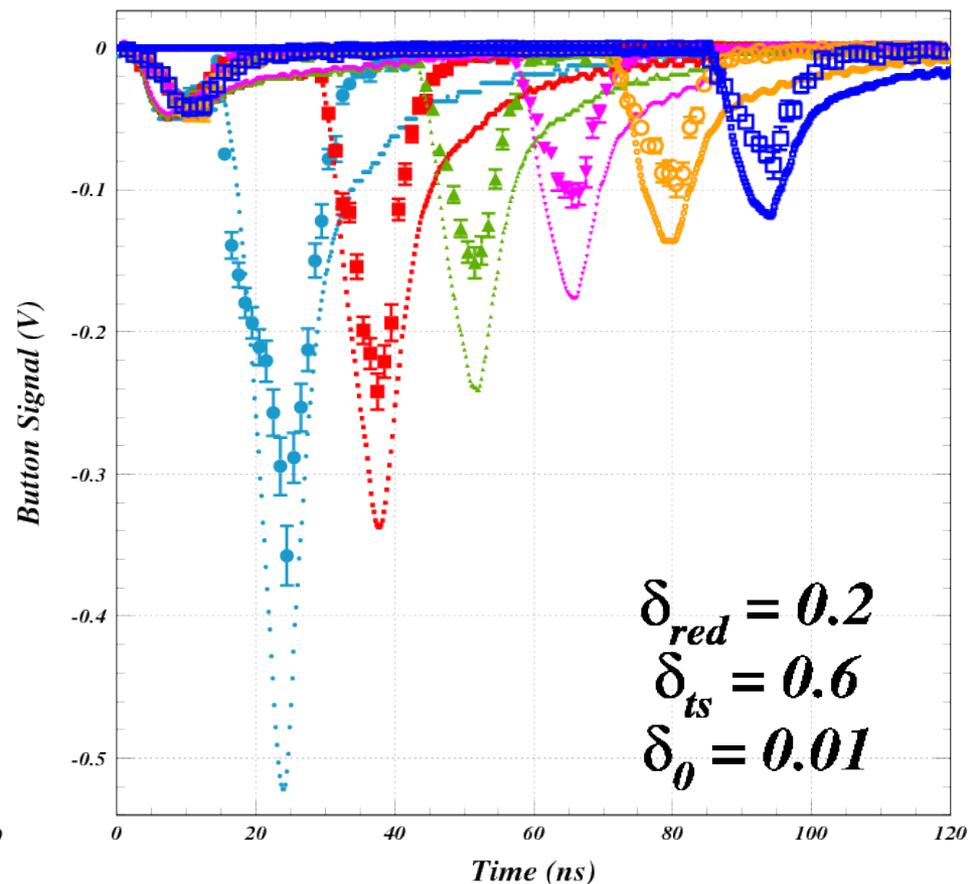
The optimal value of $\delta_{red} = 0.2$ is consistent with the value for uncoated aluminum determined by modeling coherent tune shift measurements (JAC et al, IPAC10)



Present best model for 6/18/11



Same model with 8/23/12 measurements
on unconditioned TiN



Initial indication is the quantum efficiency is similar, but there is much more cloud due to SEY.



25 data-taking sessions, more to come

2.1, 4.0, and 5.3 GeV e^+ and e^- beams

1-10 mA/bunch

Uncoated aluminum

TiN-coated aluminum

Two amorphous-carbon coatings

Diamond-like carbon coating

Unconditioned uncoated aluminum

Unconditioned TiN coating

Unconditioned a-carbon coating

4-ns, 14-ns bunch spacings up to 140 ns

Analysis continues



The witness bunch technique using the time-resolved measurements provided by shielded-pickup detectors provides remarkable discriminating power for the various contributions to electron cloud buildup.

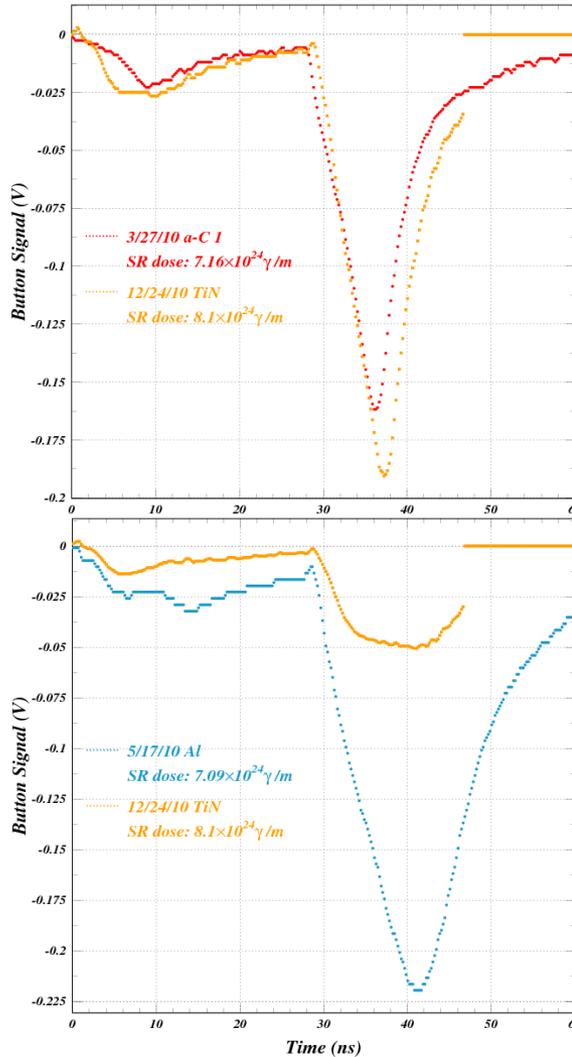
Photoelectron production characteristics are clearly distinguished from secondary electron yield processes.

The secondary yield values for the true, rediffused and elastic processes can be independently constrained with good accuracy.

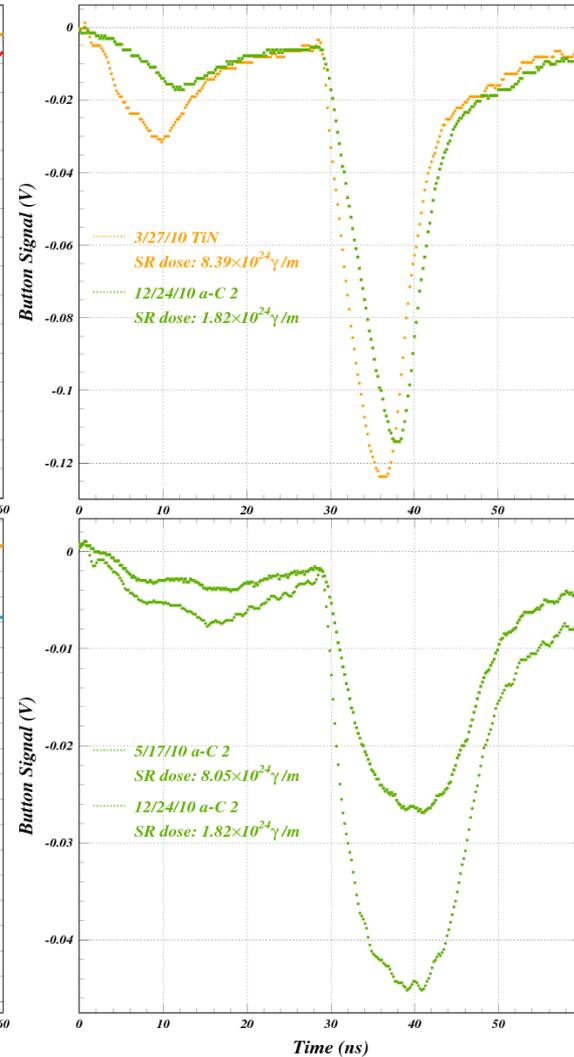
Much work remains to take advantage of the data obtained with solenoidal magnetic field and the transverse segmentation of the time-resolved RFA's.



15W



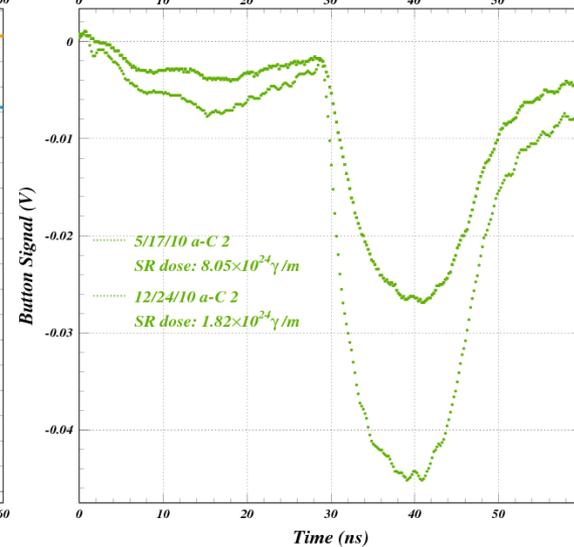
15E



5 mA/bunch

The results for the second a-carbon-coated chamber corroborate the high-energy photoelectron suppression relative to TiN observed with the first a-carbon-coated chamber.

3 mA/bunch



The second carbon-coated chamber shows conditioning effects between 5/17/10 and 12/24/10, primarily for the quantum efficiency.

The a-carbon coating suppresses high-energy photoelectrons compared to the TiN coating.

The quantum efficiency for reflected photons and the SEY are both much smaller for the TiN coating compared to uncoated aluminum.



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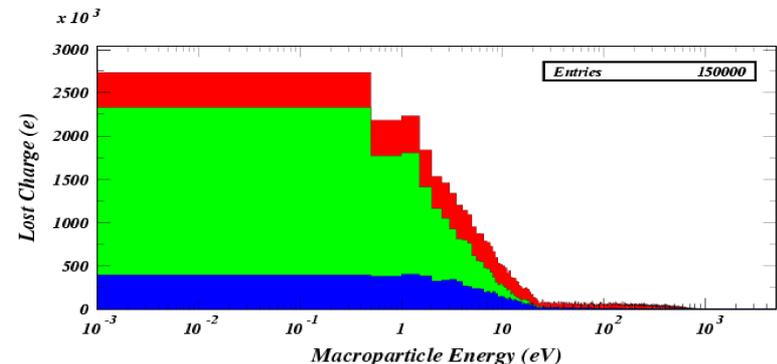
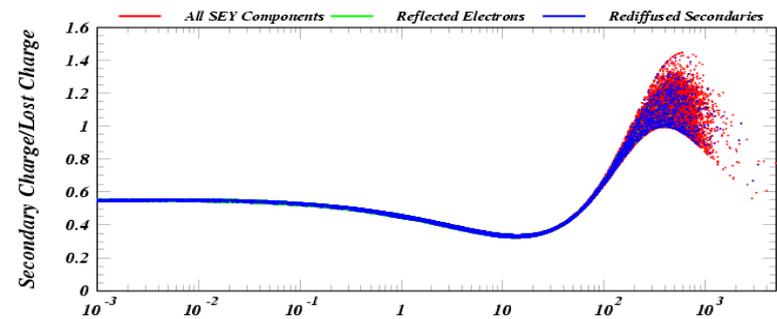
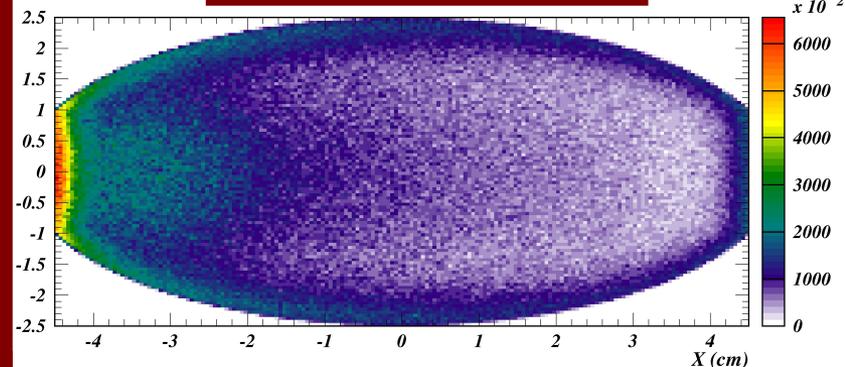
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Cloud snapshot after 14 ns

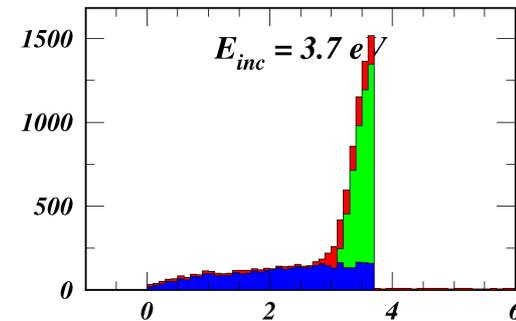
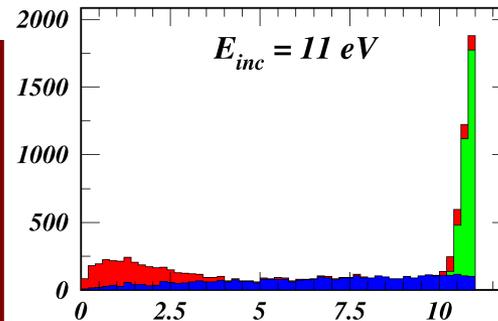
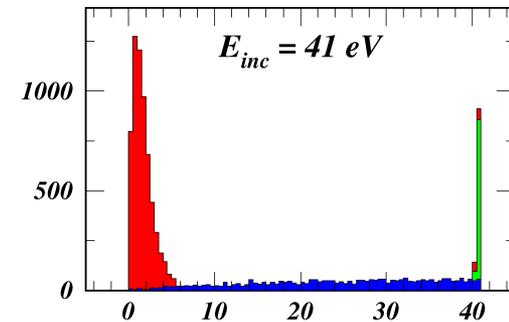
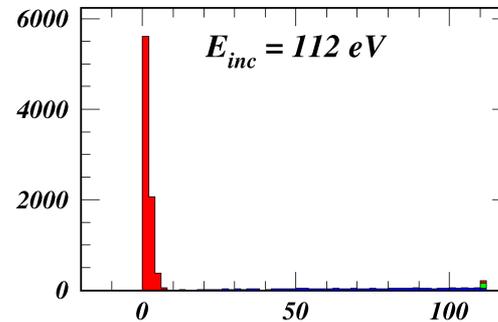
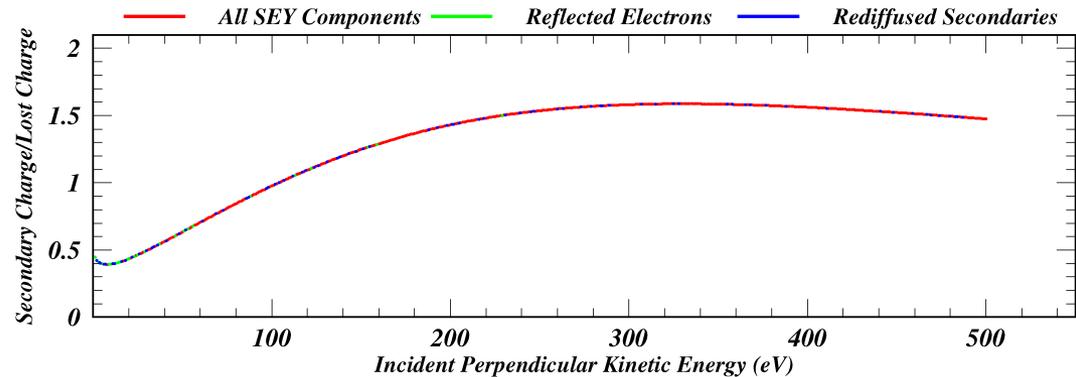
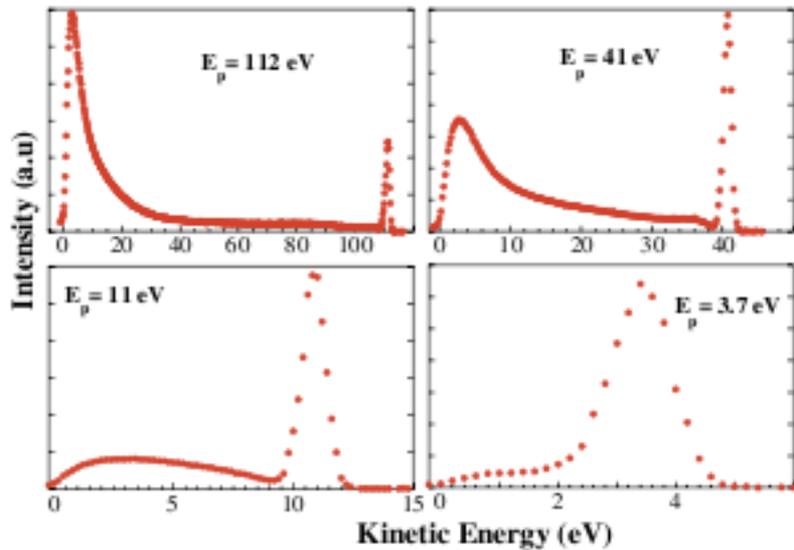




Modeled secondary electron kinetic energy distributions

Probabilistic Model for the Simulation of Secondary Electron Emission
M.A.Furman and M.F.F.Pivi, Phys. Rev. ST-AB 5, 124404 (2002)

Can Low-Energy electrons Affect High-Energy Particle Accelerators?
R.Cimino, et al, Physical Review Letters, Vol. 93, Nr. 1, 014801 (2004)



Secondary Kinetic Energy Distribution (eV)

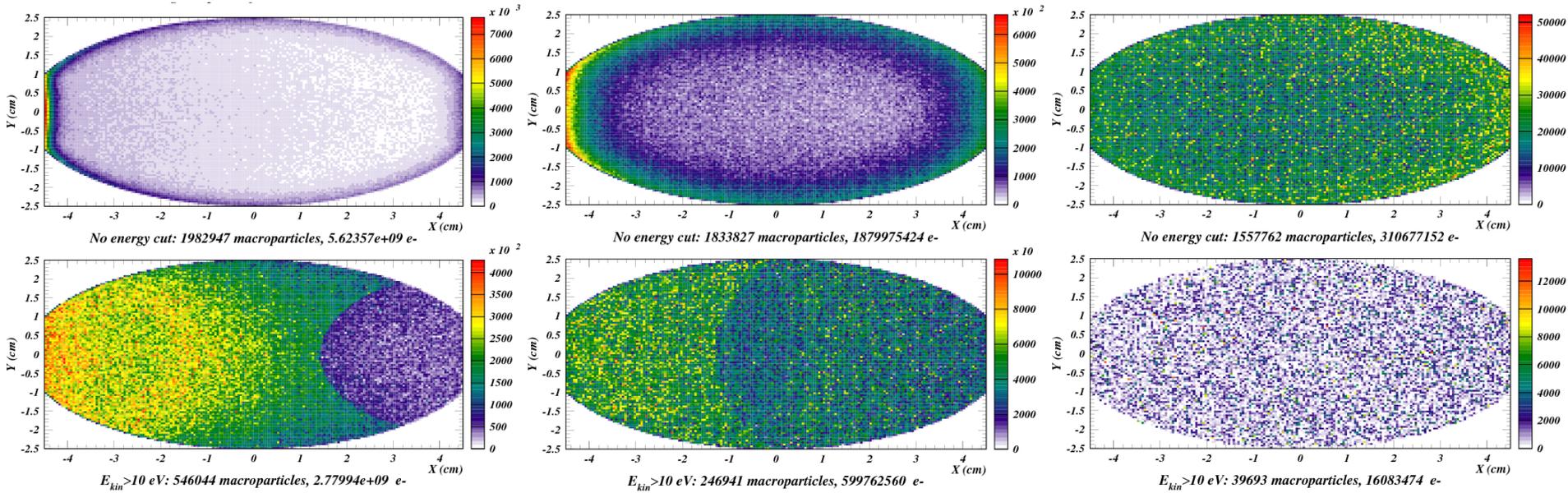
The time development of the cloud is directly dependent on secondary kinetic energies and therefore on the relative probabilities of the three secondary production processes.



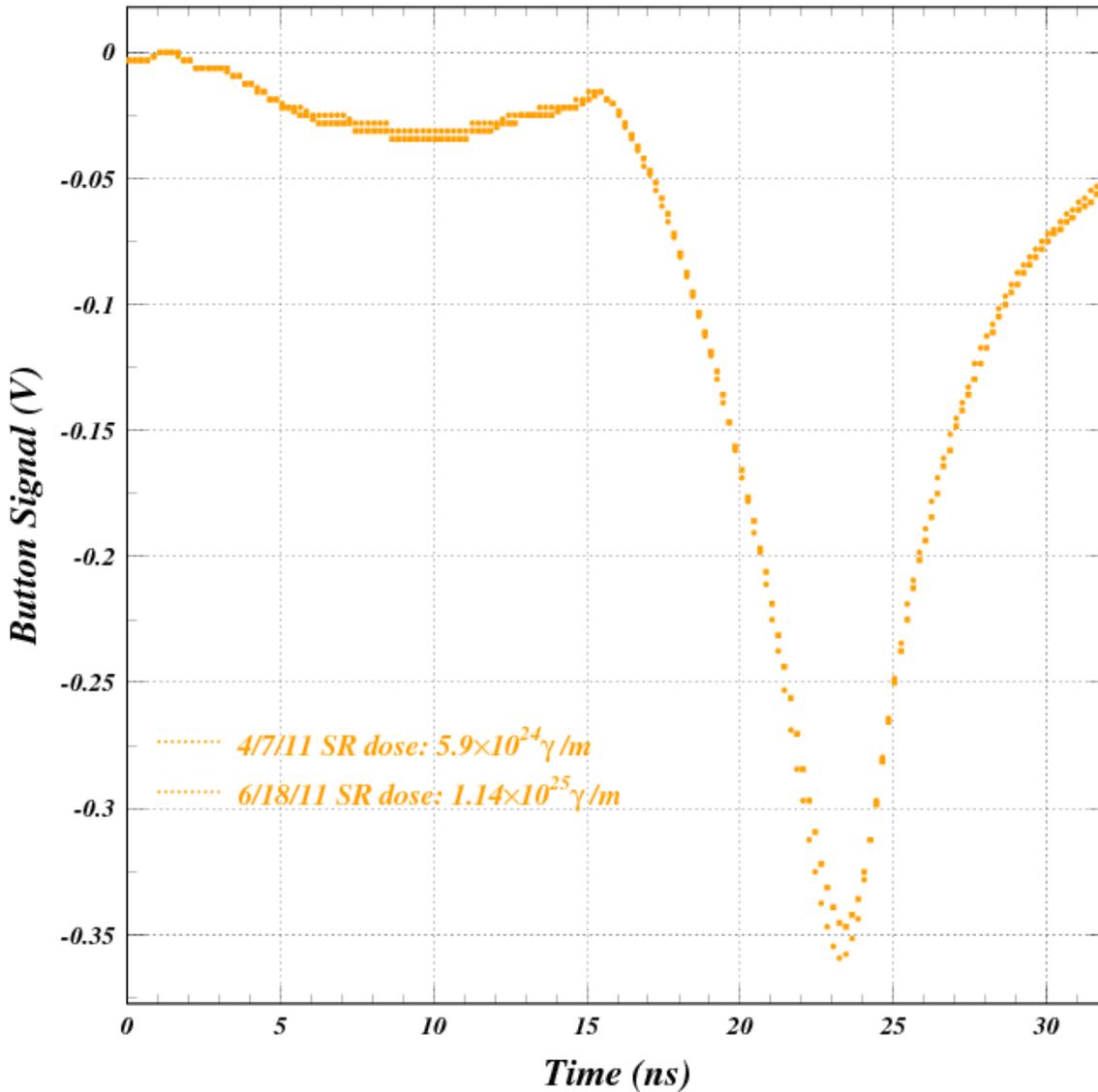
Prior to 14-ns bunch

Prior to 28-ns bunch

Prior to 84-ns bunch

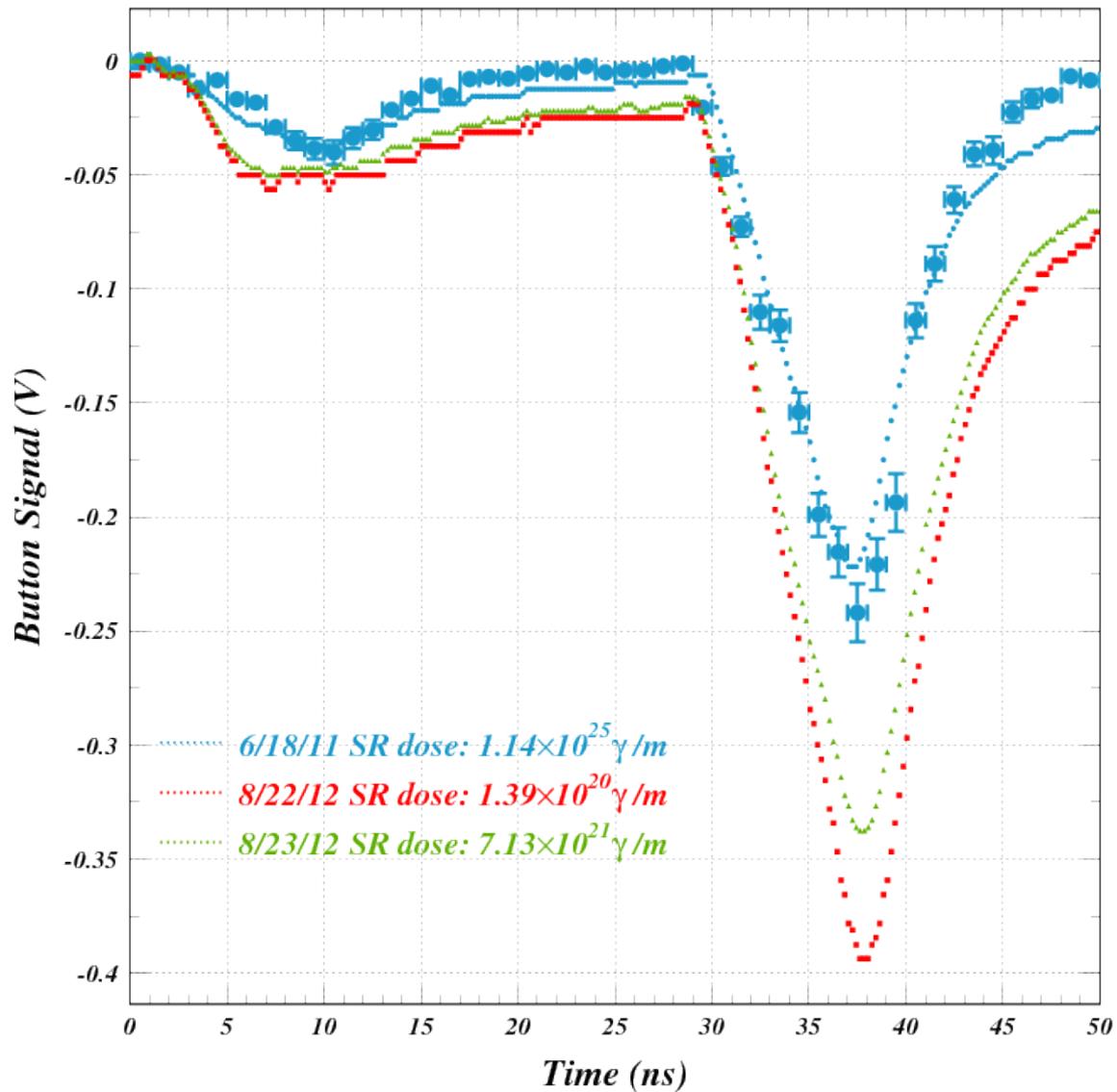


Determines the shielded-pickup signal shape and size.



Both the quantum efficiency and secondary yield for the TiN coating is remarkably stable over this range of beam conditioning.

Note also that the reproducibility of the measurement is at the level of a few percent after two months.





Date	Species	Beam Energy (GeV)	Bunch Current (mA)	15E/W	Mitigation Technique	Bunch Spacing (ns)
03/27/2010	Positrons	5.3	5	W	a-carbon (1)	14-84
	Electrons			E	TiN	
05/09/2010	Positrons	2.1	3	W	Al	4-140
	Electrons			E	a-carbon (2)	
05/17/2010	Positrons	5.3	3	W	Al	4-100
	Electrons			E	a-carbon (2)	
05/19/2010	Electrons	2.1	1	W	Al	4-120
09/21/2010	Positrons	5.3	1,2,4,6,8,10	W	TiN	14
	Electrons			E	a-carbon (2)	
09/24/2010	Positrons	2.1	2,4,6	W	TiN	14
	Electrons			E	a-carbon (2)	
12/10/2010	Electrons	2.1	1,2,3,4,5,6,8,10	W	TiN	14-84
12/20/2010	Positrons	2.1	1,2,3,4,5,6,8,10	W	TiN	56,84
12/24/2010	Positrons	5.3	3,5	W	TiN	14-84
	Electrons			E	a-carbon (2)	
04/07/2011	Positrons	5.3	1,2,3,4,5,6,8,10	W	TiN	14-84
	Electrons			E	DL carbon	
04/16/2011	Positrons	2.1	1,2,3,4,5,6,8,10	W	TiN	14-84
	Electrons			E	DL carbon	
04/17/2011	Positrons	2.1	1,2,3,4,5,6,8,10	W	TiN	14-84
	Electrons			E	DL carbon	
06/11/2011	Positrons	2.1	1,2,3,4,5,6,8,10	W	TiN	14-84
06/12/2011	Positrons	2.1	1,2,3,4,5,6,8,10	W	TiN	14-84
	Electrons			E	DL carbon	
06/18/2011	Positrons	5.3	1,2,3,4,5,6,8,10	W	TiN	14-98
	Electrons			E	DL carbon	
06/27/2011	Positrons	4.0	1,2,3,4,5,6,8,10	W	TiN	14-98
	Electrons			E	DL carbon	
09/27/2011	Positrons	5.3	1,2,3,4,5,6,8	W	TiN	84
	Electrons			E	DL carbon	
09/27/2011	Positrons	5.3	1,2,3,4,5,6,8	W	a-carbon (2)	14-84
	Electrons			E	DL carbon	
09/30/2011	Positrons	5.3	1,2,3,4,5,6,8	W	a-carbon (2)	14-84
	Electrons			E	DL carbon	
10/04/2011	Positrons	5.3	1,2,3,4,5,6,8	W	a-carbon (2)	14-84
	Electrons			E	DL carbon	
10/11/2011	Positrons	5.3	1,2,3,4,5,6,8	W	a-carbon (2)	14-84
	Electrons			E	DL carbon	
10/25/2011	Positrons	5.3	1,2,3,4,5,6,8	W	a-carbon (2)	14-84
	Electrons			E	DL carbon	
11/27/2011	Positrons	5.3	1,2,3,4,5,6,8,10	W	a-carbon (2)	14-98
	Electrons			E	DL carbon	
11/27/2011	Positrons	5.3	1,2,3,4,5,6,8,10	W	a-carbon (2)	14-84
	Electrons			E	DL carbon	

2.1, 4.0, and 5.3 GeV

Electron and positron beams

1-10 mA/bunch

Uncoated aluminum

TiN-coated aluminum

Two amorphous-carbon coatings

Diamond-like carbon coating

Unconditioned uncoated aluminum

Unconditioned TiN coating

Unconditioned a-carbon coating

4-ns, 14-ns bunch spacings up to 140 ns